
EXHIBIT R

1. A semiconductor device, comprising:

(A) a semiconductor substrate;

(B) a diffusion region which is formed in the semiconductor substrate and serves as a region for the formation of a MIS

(C) an element isolation region surrounding the diffusion region;

at least one (D) gate conductor film which is formed across the diffusion region and the element isolation region, including a gate electrode part located on the diffusion region and (D2) a gate interconnect part located on the element isolation

has (X) a constant dimension in a gate length direction;

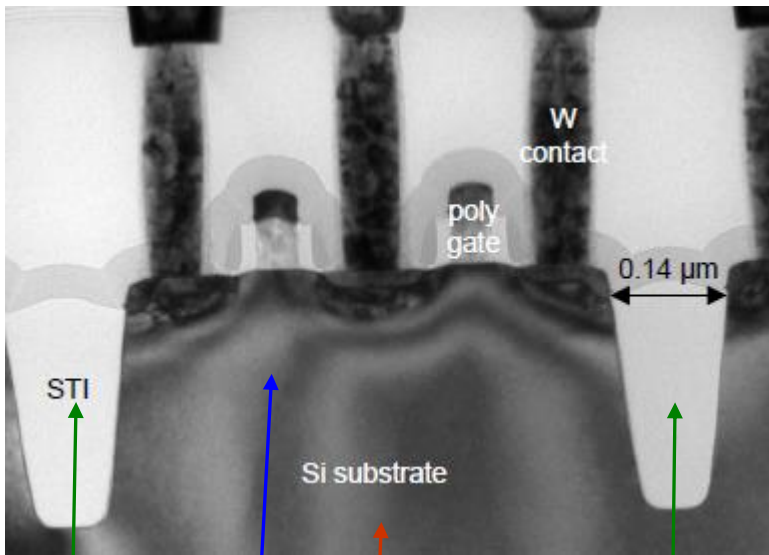
(E) an interlayer insulating film covering (D1) the gate electrode part; and

(F) a gate contact which passes through the (E) interlayer insulating film, is connected to (D2) the gate interconnect part and has a dimension in the gate length direction larger than (D2) the gate interconnect part.

Claim 1

A semiconductor device, comprising: (A) a semiconductor substrate; (B) a diffusion region which is formed in the substrate and serves as a region for the formation of a MIS transistor; (C) an element isolation region surrounding the region;

(Cross section : gate length direction)



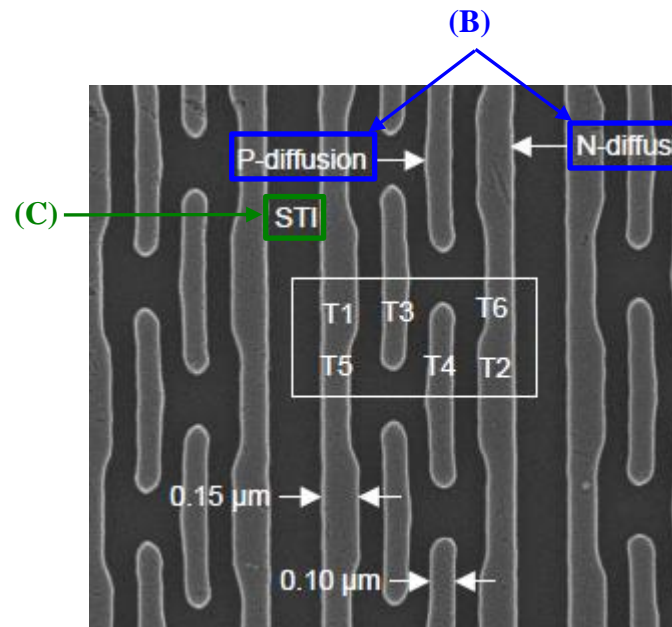
(C)

(B)

(A)

(C)

(Plane : diffusion level)



(B)

P-diffusion

N-diffusion

STI

T1 T3 T6
T5 T4 T2

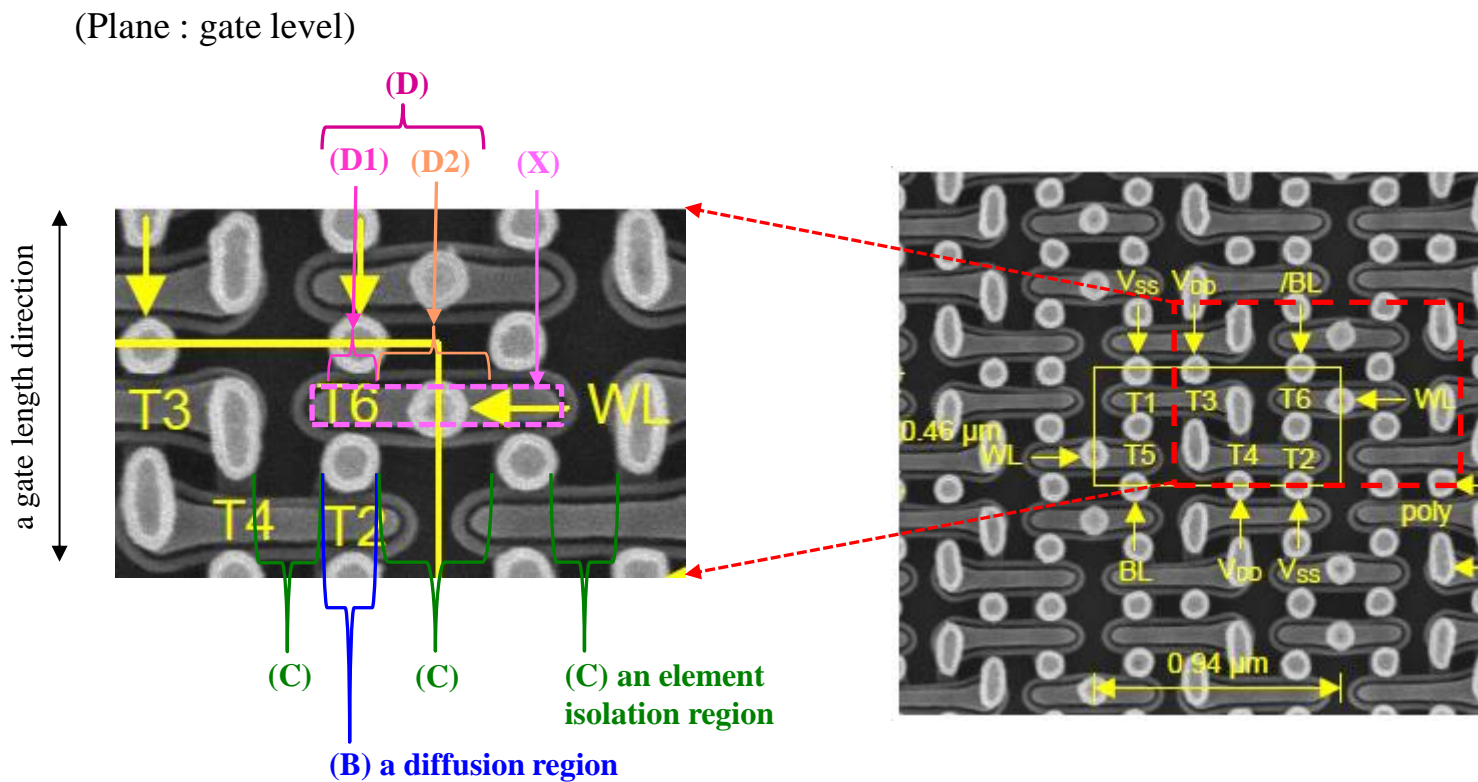
0.15 μm

0.10 μm

(C)

Claim 1

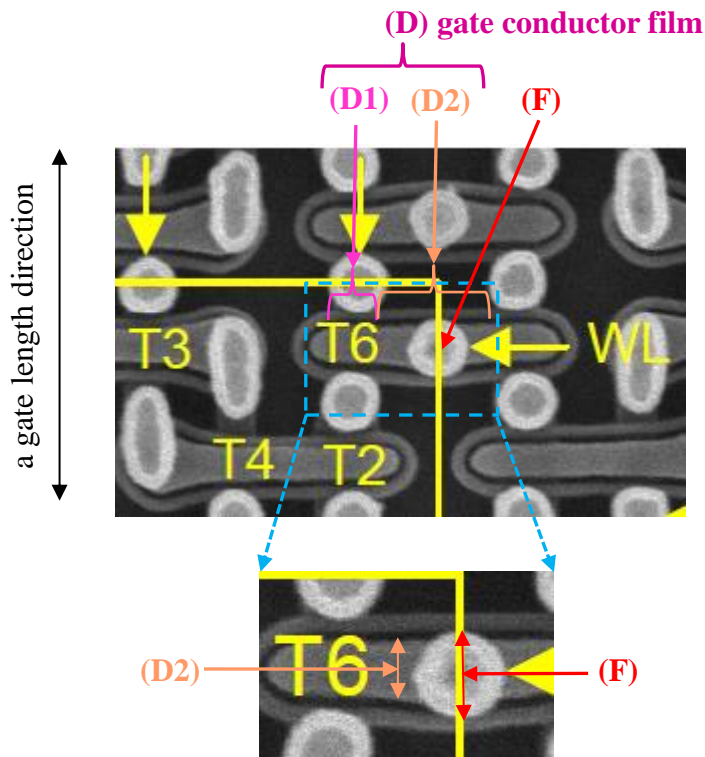
at least one **(D) gate conductor film** which is formed across the diffusion region and the element isolation region, including **gate electrode part** located on the diffusion region and **(D2) a gate interconnect part** located on the element isolation region, has **(X) a constant dimension** in a gate length direction;



Claim 1

(E) an interlayer insulating film covering (D1) the gate electrode part; and
 (F) a gate contact which passes through the (E) interlayer insulating film, is connected to (D2) the gate interconnect
 a dimension in the gate length direction larger than (D2) the gate interconnect part.

(Plane : gate level)



(Cross section : gate length direction)

